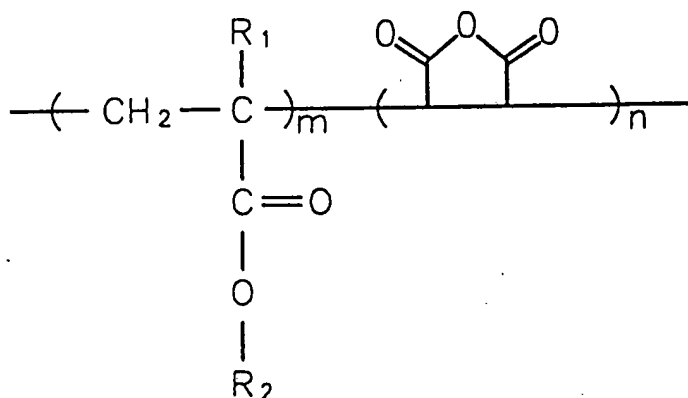


## Amendments to the Claims

This listing of claims will replace all prior versions, and listings, of claims in the application:

### Listing of Claims:

1. (currently amended): A photosensitive copolymer having a weight-average molecular weight of 3,000 to 100,000 and consisting essentially of first and second monomers represented by the following formulae:



wherein R<sub>1</sub> is a hydrogen atom or methyl, R<sub>2</sub> is an acid-labile tertiary alkyl group, m/(m+n) is 0.5 to 0.8, ~~and m+n=1~~, and

wherein R<sub>2</sub> is 2-methyl-2-norbornyl, 2-ethyl-2-norbornyl, 2-methyl-2-isobornyl, 2-ethyl-2-isobornyl, 8-methyl-8-tricyclo[5.2.1.0<sup>2,6</sup>]decanyl, or 8-ethyl-8-tricyclo[5.2.1.0<sup>2,6</sup>]decanyl.

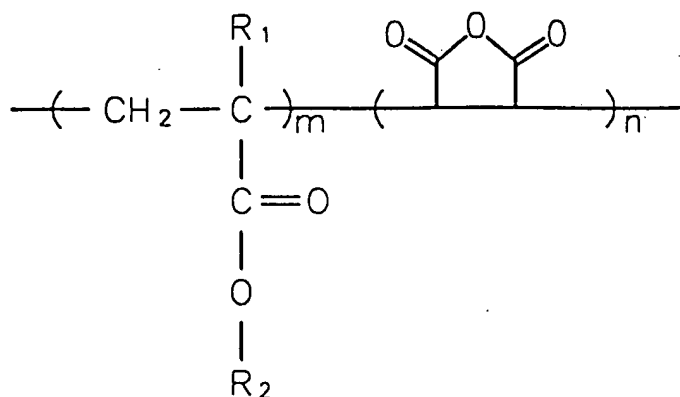
2. (original): The photosensitive copolymer according to claim 1, wherein the photosensitive polymer has a weight-average molecular weight of 5,000 to 30,000.

3. (canceled).

4. (original): The photosensitive copolymer according to claim 1, wherein  $R_2$  is 2-methyl-2-norbornyl, 2-ethyl-2-norbornyl, 2-methyl-2-isobornyl, 2-ethyl-2-isobornyl, 8-methyl-8-tricyclo[5.2.1.0<sup>2,6</sup>]decanyl, 8-ethyl-8-tricyclo[5.2.1.0<sup>2,6</sup>]decanyl, 2-methyl-2-adamantyl, or 2-ethyl-2-adamantyl.

5. (currently amended): A resist composition comprising:

(a) a photosensitive copolymer having a weight-average molecular weight of 3,000 to 100,000 and consisting essentially of first and second monomers represented by the following formulae:



wherein  $R_1$  is a hydrogen atom or methyl,  $R_2$  is an acid-labile tertiary alkyl group,  $m/(m+n)$  is 0.5 to 0.8, ~~and  $m+n=1$~~ , and wherein  $R_2$  is 2-methyl-2-norbornyl, 2-ethyl-2-norbornyl, 2-methyl-2-isobornyl, 2-ethyl-2-isobornyl, 8-methyl-8-tricyclo[5.2.1.0<sup>2,6</sup>]decanyl, or 8-ethyl-8-tricyclo[5.2.1.0<sup>2,6</sup>]decanyl; and

(b) a photoacid generator (PAG).

6. (original): The resist composition according to claim 5, wherein the photosensitive polymer has a weight-average molecular weight of 5,000 to 30,000.

7. (canceled).

8. (canceled).
9. (original): The resist composition according to claim 5, wherein the PAG is contained in an amount of 1.0 to 15% by weight based on the total weight of the copolymer.
10. (original): The resist composition according to claim 9, wherein the PAG is selected from the group consisting of triarylsulfonium salts, diaryliodonium salts, sulfonates or mixtures thereof.
11. (original): The resist composition according to claim 10, wherein the PAG is triphenylsulfonium triflate, diphenyliodonium triflate, triphenylsulfonium nonaflate, diphenyliodonium nonaflate, triphenylsulfonium antimonate, diphenyliodonium antimonate, di-t-butyl diphenyliodonium triflate, N-succinimidyl triflate, 2,6-dinitrobenzyl sulfonate, or a mixture thereof.
12. (original): The resist composition according to claim 5, further comprising an organic base.
13. (original): The resist composition according to claim 12, wherein the organic base is contained in an amount of 0.01 to 2.0% by weight based on the total weight of the copolymer.

14. (original): The resist composition according to claim 13, wherein the organic base is triethylamine, triisobutylamine, trioctylamine, diethanolamine, triethanolamine or a mixture thereof.
15. (original): The resist composition according to claim 5, further comprising a surfactant.
16. (original): The resist composition according to claim 15, wherein the surfactant is contained in an amount of 50 to 500 ppm.
17. (original): The resist composition according to claim 15, wherein the surfactant is polyether or polysulfonate.
18. (original): The resist composition according to claim 17, wherein the surfactant is poly(ethylene glycol).